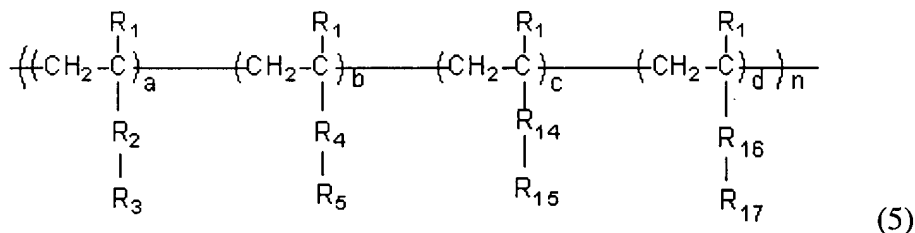


Amendments to the Abstract:

On page 38, line 1 through page 39, line 12, please replace the Abstract with the following:

ABSTRACT OF THE DISCLOSURE

A polymer for a chemically amplified negative photoresist and a photoresist composition are provided. A representative polymer of the invention is a compound of formula 5:

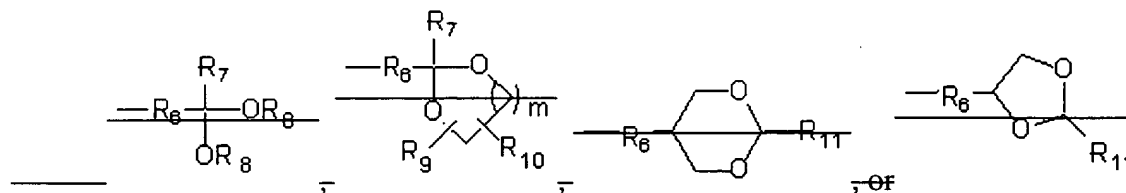


wherein:

— R_1 is H or CH_3 ;

— R_2 and R_4 are each independently $(\text{R})_\alpha(\text{CH}_2)_\beta\text{R}'$ or $(\text{R})_\alpha[(\text{CH}_2)_\gamma\text{O}]_\delta\text{R}'$ (wherein, R is CO, CO_2 , O, OCO, or OCO_2 , R' is O, CO_2 , or OCO_2 , α is 0 or 1, β is 0 to 5, γ is 1 or 2, and δ is 1 to 5);

— R_3 is represented by one of the formula:

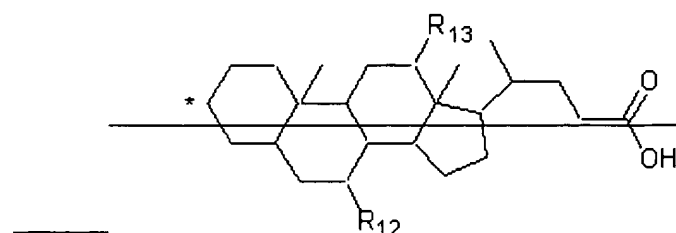


— wherein R_6 , which combines an acetal compound and a vinyl compound, is a C_4 - C_5 -saturated alkyl, a C_4 - C_5 -ether, or a C_4 - C_5 -carbonyl; R_7 to R_{11} are each independently selected

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from H, C₁-C₅-saturated alkyls, C₁-C₅-ethers, C₁-C₅-carbonyl groups, and C₁-C₅-alcohol groups;
 and m is a number ranging from 1-5; and

_____ R₅ is represented by formula:



_____ wherein R₁₂ and R₁₃ are each independently H or OH; and

_____ * represents the bonding site at which the R₄ group is bonded.

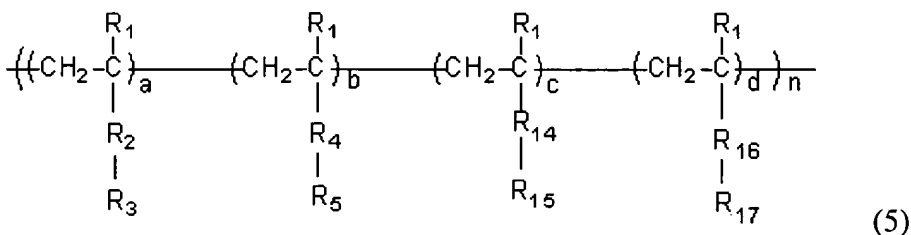
_____ R₁₄ and R₁₆ are each independently selected from a single bond (R)_α(CH₂)_βR' and
 (R)_α[(CH₂)_γO]_δR' (wherein, R is CO, CO₂, O, OCO, or OCO₂, R' is O, CO₂, or OCO₂, α is 0 or
 1, β is 0 to 5, γ is 1 or 2, and δ is 1 to 5); R₁₅ is a hydroxyl group; R₁₇ is a carboxyl group;

_____ R₁ through R₅ and R₁₄ through R₁₇ are defined as set forth in the specification, and a, b, c,
 and d represent the mole ratios of each monomer, wherein a has a value of 0-0.5, b has a value of
 0-0.9, c has a value of 0-0.3, and d has a value of 0-0.3, provided that a+b+c+d = 1; and

_____ n represents the degree of polymerization of each polymer, and has a value of at least 2.

ABSTRACT OF THE DISCLOSURE

A polymer for a chemically amplified negative photoresist and a photoresist composition are provided. A representative polymer of the invention is a compound of formula 5:



wherein: R₁ through R₅ and R₁₄ through R₁₇ are defined as set forth in the specification, and a, b, c, and d represent the mole ratios of each monomer, wherein a has a value of 0-0.5, b has a value of 0-0.9, c has a value of 0-0.3, and d has a value of 0-0.3, provided that a+b+c+d = 1; and n represents the degree of polymerization of each polymer, and has a value of at least 2.